SIMULATION USING DESIGN GEOMETRY INFORMATION
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ABSTRACT

Design geometry information from an area outside the area of interest (AOI) on a mask can be combined with inspection information from the AOI to facilitate an accurate, simulated wafer image. The design geometry information can be easily generated or accessed, thereby ensuring an uninterrupted inspection process and minimizing the associated storage costs for the simulation process. The design geometry information can be pseudo design geometry information or actual design geometry information.